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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/743,265	12/23/2003	Levinus Pieter Bakker	081468-0307392	4468
909	7590 08/24/2006		EXAMINER	
PILLSBUR	Y WINTHROP SHAV	JOHNSTON, PHILLIP A		
P.O. BOX 10500 MCLEAN, VA 22102			ART UNIT	PAPER NUMBER
			2881	

DATE MAILED: 08/24/2006

Please find below and/or attached an Office communication concerning this application or proceeding.

				6/				
Office Action Summan		Application No.	Applicant(s)					
		10/743,265	BAKKER ET AL.					
	Office Action Summary	Examiner	Art Unit					
		Phillip A. Johnston	2881					
Period f	The MAILING DATE of this communication app or Reply	pears on the cover shee	t with the correspondence ad	dress				
WHI - Extended aftended - If N - Fail Any	HORTENED STATUTORY PERIOD FOR REPLY CHEVER IS LONGER, FROM THE MAILING Discussions of time may be available under the provisions of 37 CFR 1.1 r SIX (6) MONTHS from the mailing date of this communication. O period for reply is specified above, the maximum statutory period vure to reply within the set or extended period for reply will, by statute reply received by the Office later than three months after the mailing and patent term adjustment. See 37 CFR 1.704(b).	ATE OF THIS COMMUM 36(a). In no event, however, may will apply and will expire SIX (6) and application to become	JNICATION.  By a reply be timely filed  MONTHS from the mailing date of this co					
Status								
1)⊠	Responsive to communication(s) filed on 21 M	lav 2004						
		action is non-final.						
	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is							
.—	closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.							
Disposit	tion of Claims							
4)⊠	Claim(s) 1-24 is/are pending in the application.							
/—	4a) Of the above claim(s) is/are withdrawn from consideration.							
5)[	Claim(s) is/are allowed.							
6)⊠	∑ Claim(s) <u>1-24</u> is/are rejected.							
7)	Claim(s) is/are objected to.							
8)[	Claim(s) are subject to restriction and/o	r election requirement.						
Applicat	ion Papers							
9)	The specification is objected to by the Examine	r.						
	The drawing(s) filed on 23 December 2003 is/a		o)  objected to by the Exam	iner.				
	Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).							
	Replacement drawing sheet(s) including the correct			R 1.121(d).				
11)[	The oath or declaration is objected to by the Ex	raminer. Note the attac	hed Office Action or form PT	O-152.				
Priority	under 35 U.S.C. § 119							
	Acknowledgment is made of a claim for foreign   ☐ All b)☐ Some * c)☐ None of:		C. § 119(a)-(d) or (f).					
	1. Certified copies of the priority documents							
	2. Certified copies of the priority documents			0.				
	3. Copies of the certified copies of the prior		en received in this National	Stage				
* 9	application from the International Bureau See the attached detailed Office action for a list		not received					
·	see the attached detailed office action for a list	or the certified copies	not received.					
Attachmer	• •							
	ce of References Cited (PTO-892) ce of Draftsperson's Patent Drawing Review (PTO-948)		ew Summary (PTO-413) No(s)/Mail Date					
3) 因 Info <i>i</i>	ce of Draftsperson's Patent Drawing Review (PTO-948) mation Disclosure Statement(s) (PTO-1449 or PTO/SB/08) er No(s)/Mail Date <u>#</u> 2004; 10-2005.		of Informal Patent Application (PTO	)-152)				
S. Patent and	Frademark Office	<del></del>						

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### **Detailed Action**

## **Double Patenting**

1. The nonstatutory double patenting rejection is based on a judicially created doctrine grounded in public policy (a policy reflected in the statute) so as to prevent the unjustified or improper timewise extension of the "right to exclude" granted by a patent and to prevent possible harassment by multiple assignees. See *In re Goodman*, 11 F.3d 1046, 29 USPQ2d 2010 (Fed. Cir. 1993); *In re Longi*, 759 F.2d 887, 225 USPQ 645 (Fed. Cir. 1985); *In re Van Ornum*, 686 F.2d 937, 214 USPQ 761 (CCPA 1982); *In re Vogel*, 422 F.2d 438, 164 USPQ 619 (CCPA 1970);and, *In re Thorington*, 418 F.2d 528, 163 USPQ 644 (CCPA 1969).

A timely filed terminal disclaimer in compliance with 37 CFR 1.321(c) may be used to overcome an actual or provisional rejection based on a nonstatutory double patenting ground provided the conflicting application or patent is shown to be commonly owned with this application. See 37 CFR 1.130(b).

Effective January 1, 1994, a registered attorney or agent of record may sign a terminal disclaimer. A terminal disclaimer signed by the assignee must fully comply with 37 CFR 3.73(b).

2. Claims 1-24 are rejected under the judicially created doctrine of obviousness-type double patenting as being unpatentable over claims 1-15 of U.S. Patent No. 6,838,684; and claims 1-23 of U.S. Patent No. 7,034,308, since each discloses a lithography system having a vaned or channeled barrier to prevent debris emitted from a radiation source from striking a substrate during patterning.

## Claims Rejection – 35 U.S.C. 103

3. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was

made to a person having ordinary skill in the art to which the subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

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4. Claims 1-24 are rejected under 35 U.S.C. 103(a) as being unpatentable over U.S. Patent No. 6,867,843, to Ogushi, in view of Partlo, U.S. Patent No. 6,452,199.

Regarding claims 1,16-18, 20-22, and 24 Ogushi (843) discloses in Figure 1 a debris removal system 100 having an attracting unit positioned between the source 806 and the projection optics 840 of lithography system 10, where an attracting unit is equipped with plural vanes 130 (lamellas), which catch debris on fin surfaces 132. See Column 7, line 1-26; Figures 2A, 2B, and 3 below.

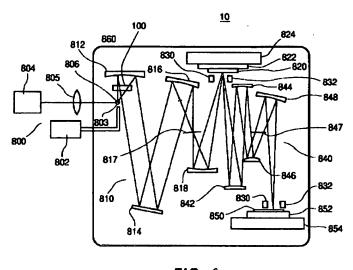


FIG. 1

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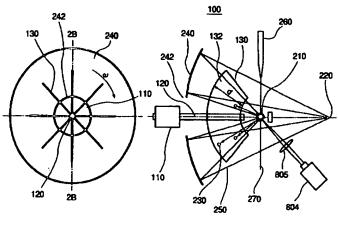


FIG. 2A

FIG. 2B

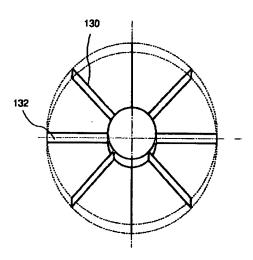


FIG. 3

Regarding the "slidably connected" limitation of claims 1,15-18,20,22, and 24, the examiner has reviewed Figure 2A and Figure 3 above, and concluded that, it would have been obvious to one of ordinary skill that the attracting unit has both inner and outer rings, where the rings appear to have slots for the vanes to be slidably connected as means for assembling the structure.

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Although Ogushi (843) generally discloses thermal design considerations for a debris removal system in a high temperature plasma environment, Ogushi (843) fails to specifically disclose the thermal shielding limitations of claims 2-15, 19,21, and 23. However, Partlo (199) discloses a conical debris collector 5 comprised of nested conical sections that is attached to or is a part of radiation collector-director 4. The conical nested debris collector and the radiation collector-director are maintained at a temperature in the range of about 400°C. Both collectors are comprised of nickel plated substrates. The radiation collector-director portion 4 is coated with molybdenum or rhodium for very high reflectivity, as recited in claims 19,21, and 23. Also lightpipe 6 is a hollow lightpipe (shield) which employs substantially total external reflection on its inside surfaces, as recited in claims 2-15. See Column 6, line 60-68; Column 7, line 1-44; Column 11, line 7-13; and Figure 9 below.

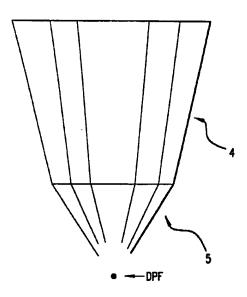


FIG.9

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Therefore it would have been obvious to one of ordinary skill in the art that the debris removal system of Ougshi (843) could be modified too use the debris collector of Partlo (1999) to provide an external reflection radiation collector-director, where debris is collected and kept from depositing on the illumination optics of the lithography tool.

### Conclusion

5. Any inquiry concerning this communication or earlier communications should be directed to Phillip Johnston whose telephone number is (571) 272-2475. The examiner can normally be reached on Monday-Friday from 6:30 am to 3:00 pm. If attempts to reach the examiner by telephone are unsuccessful, the examiners supervisor John Lee can be reached at (571) 272-2477. The fax phone number for the organization where the application or proceeding is assigned is 571 273 8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

PJ

August 16, 2006

Nikita WELLS
PRIMARY EXAMINER

08/18/06

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